

IN THE CLAIMS

26. A method of forming a cantilever probe contactor, the method comprising:
patterning a first and second sacrificial layer over a substrate, each layer having an
opening, wherein the substrate, the first sacrificial layer and the second sacrificial layer are
arranged in this order;
depositing a first conductive material after patterning the first sacrificial layer;
depositing a second conductive material after patterning the second sacrificial layer to
form a cantilever element having:
a first portion formed in an opening in the first sacrificial layer,
a second portion comprising a support element coupled to the first portion and
formed in an opening in the second sacrificial layer, and
a third portion comprising a contact element coupled to the first portion, at least a part
of the third portion being formed in the substrate, wherein the contact element is a contact
section which is to contact with an electrode pad of an object to be checked; and
removing the first and second sacrificial layers simultaneously,
wherein the contact element is formed of a third conductive material in a
predetermined opening formed in the substrate.

27. The method of claim 26, wherein the substrate is a silicon substrate.

28. The method of claim 26, wherein the first conductive material and the second
conductive material include at least nickel.

29. The method of Claim 26, wherein the number of sacrificial layers is at least two.

30. The method of Claim 26, wherein the third portion is formed of a material different from that forming the first portion and the second portion.

31. The method of Claim 26, wherein the first and second sacrificial layers are respectively formed of resist layers having different thicknesses.